

# Machine Learning and Pattern Matching in Physical Design

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<http://www.cerc.utexas.edu/utda>

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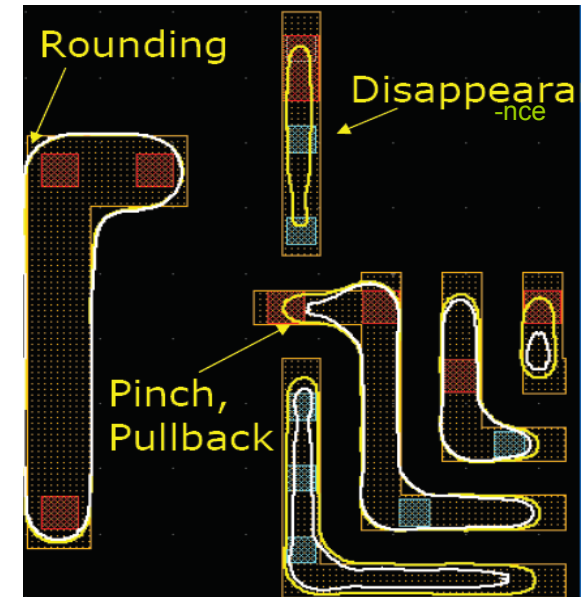
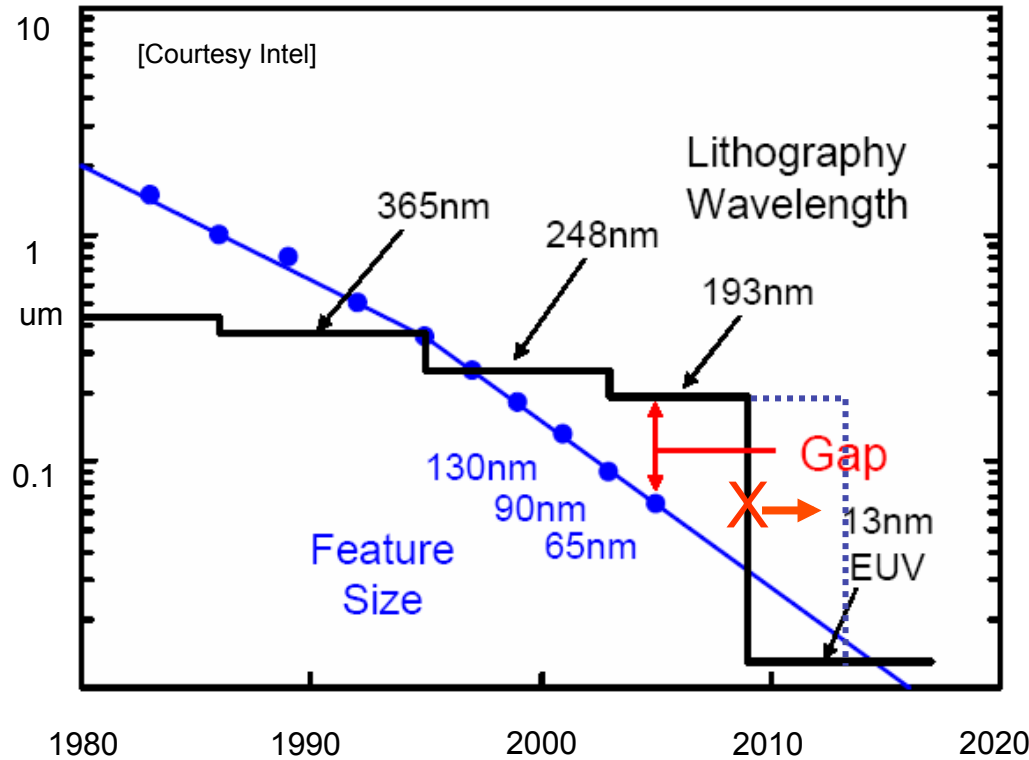
# Outline

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- ◆ Modern VLSI Challenges
- ◆ Machine Learning and Pattern Matching 101
- ◆ Applications in VLSI Design and Verification
- ◆ Some Advanced Issues
- ◆ Conclusion

# VLSI Manufacturing Challenges



- ◆ The industry forced to extend 193nm lithography
  - › Feature size is much smaller than the wavelength
  - › Deep sub-wavelength design and manufacturing

# Machine Learning 101

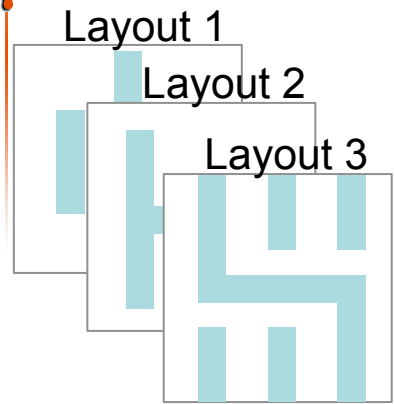
- ◆ Study of algorithms that can learn from data

$$y=f(x)$$

y : output  
x : input data  
f : function

- ◆ Supervised learning (labels (y) are given)
  - › Classification : y is categorical data
  - › Regression : y is continuous data
- ◆ Unsupervised learning (no labels are given)
  - › Clustering, etc.

# Machine Learning 101 (cont'd)

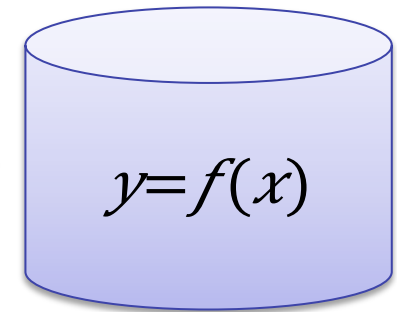


Learning data

Abstracted vector data

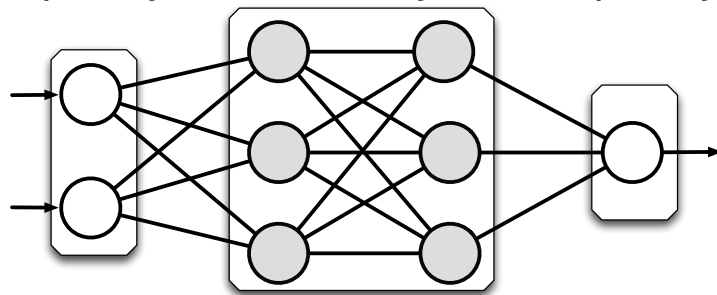
$x_1 = (0, 1, 0, 1.5, \dots)$   
 $x_2 = (2, 0.5, 0.1, -1, \dots)$   
 $x_3 = (1, -1, 0, 0.3, \dots)$   
.....

Feature extraction



Model training

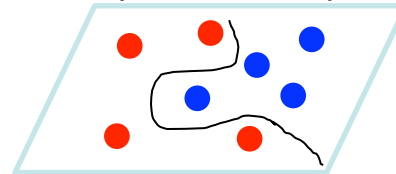
Input layer Hidden layers Output layer



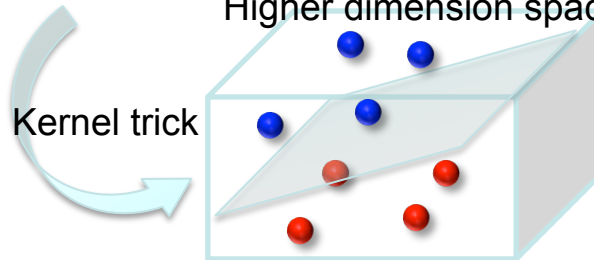
**ANN**

(Artificial Neural Network)

Input feature space



Higher dimension space

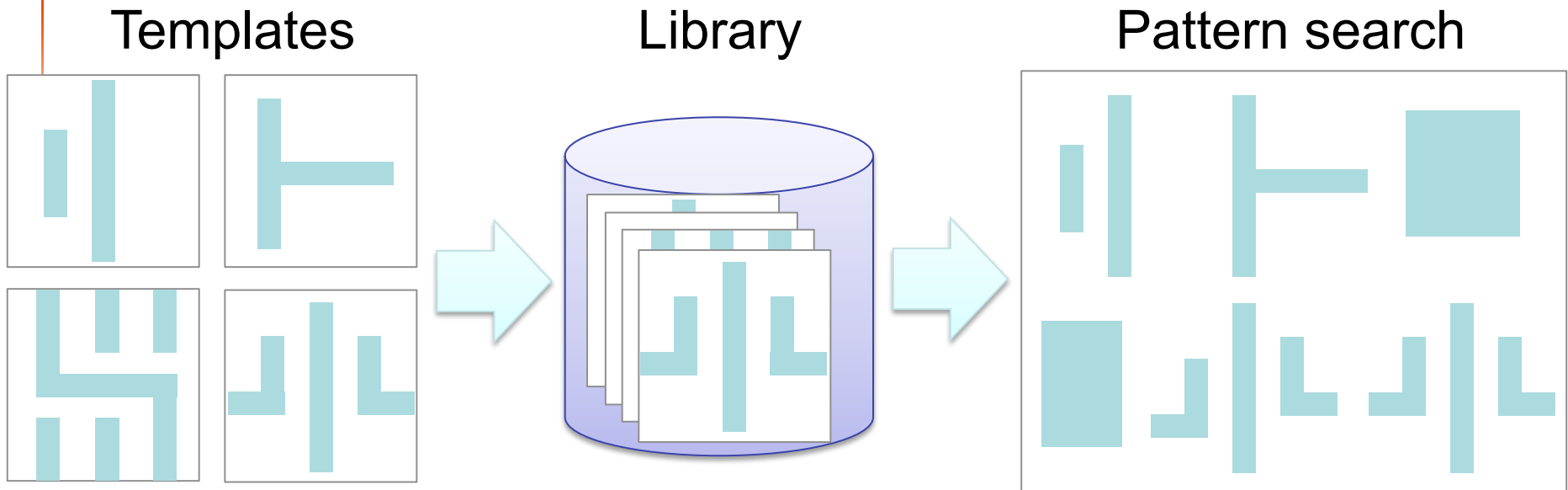


**SVM**

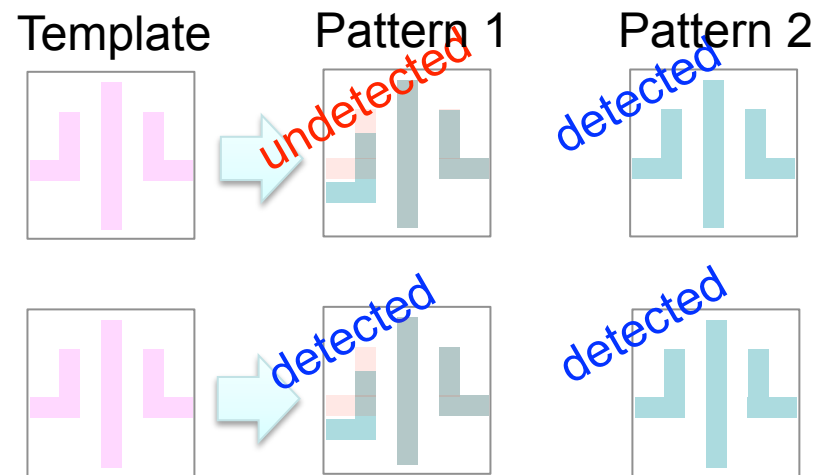
(Support Vector Machine)

**Boosting ...**

# Pattern Matching 101



- ◆ Exact Pattern Matching
  - > Detected pattern = template
  - >
- ◆ Fuzzy Pattern Matching
  - > Detected pattern  $\approx$  template

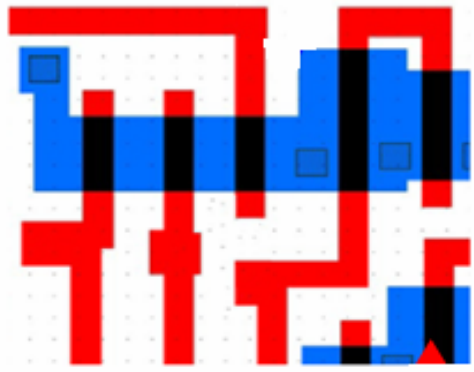


# Outline

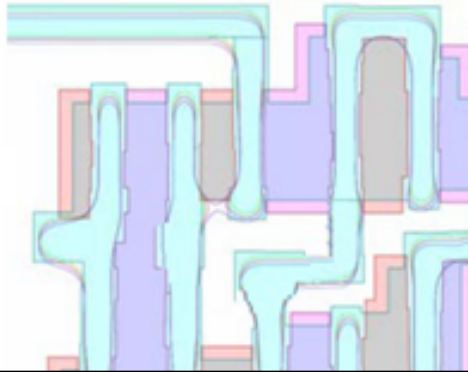
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- ◆ Modern VLSI Challenges
- ◆ Machine Learning and Pattern Matching 101
- ◆ Applications in VLSI Design and Verification
  - › Lithography Hotspot Detection
  - › Lithography Friendly Routing
  - › Datapath Extraction and Placement
- ◆ Some Advanced Issues
- ◆ Conclusion

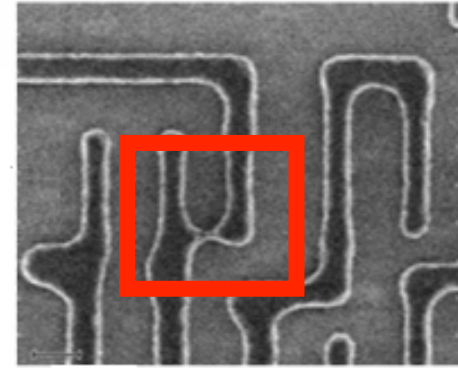
# Lithography Hotspot Detection



**Layout**



**Litho simulations**



**Chip**

## ◆ Lithographic hotspots

- › What you see (at design) is NOT what you get (at fab)
- › Hotspots mean poor printability
- › Highly dependent on manufacturing conditions
- › Exist after resolution enhancement techniques

## ◆ Litho-simulations are extremely CPU intensive

- › Full-blown OPC could take a week
- › Impossible to be used in inner design loop



# Various Approaches

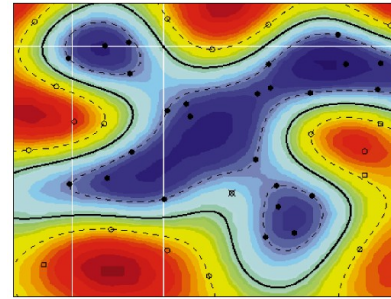
[Xu+ ICCAD07]  
[Yao+ ICCAD08,  
[Khang SPIE06],  
etc.



## Pattern/Graph Matching

### ◆ Pros and cons

- › Accurate and fast for known patterns
- › But too many possible patterns to enumerate
- › Sensitive to changing manufacturing conditions
- › High overshoot (false-alarms)



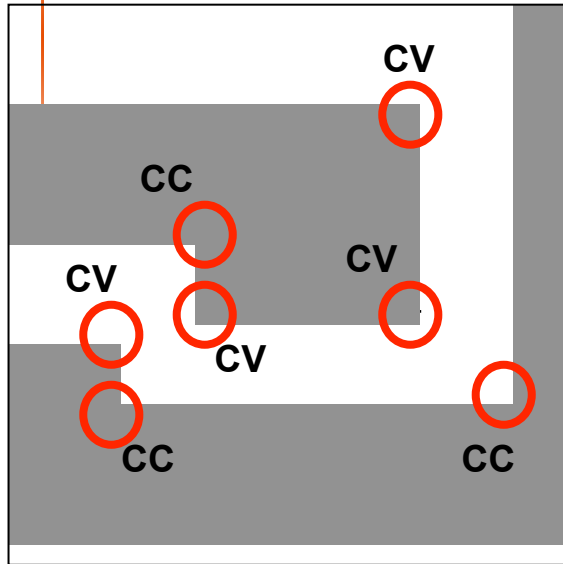
**SVM** [J. Wu+ SPIE09]  
[Drmanac+ DAC09]  
**Neural Network Model**  
[Norimasa+ SPIE07][Ding  
+ ICICDT09]  
**Regression Model**  
[Torres+ SPIE09]

## Data Mining/Machine Learning

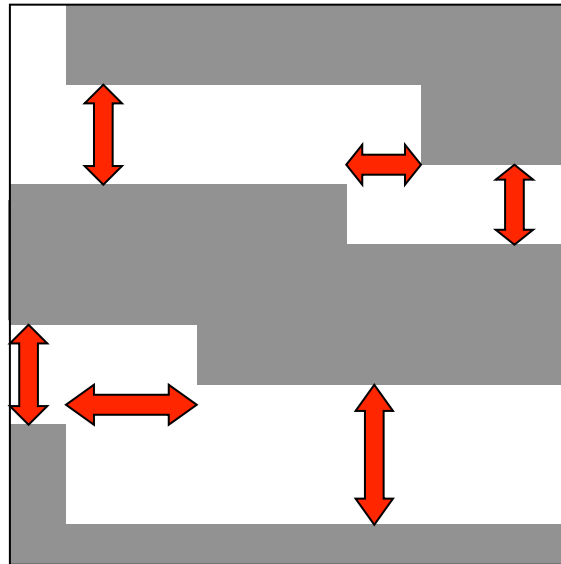
### ◆ Pros and cons

- ◆ Good to detect unknown or unseen hotspots
- ◆ Accuracy may not be good for “seen” patterns (cf. PM)
- › Hard to trade-off accuracy and false alarms

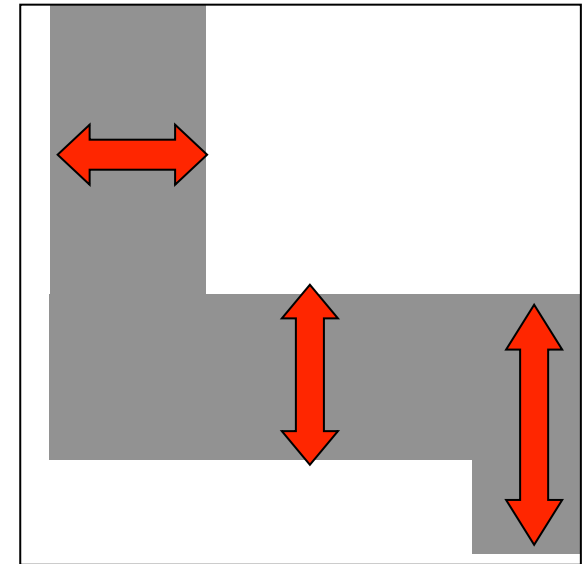
# Layout Analysis



(a) Corner information



(b) External length



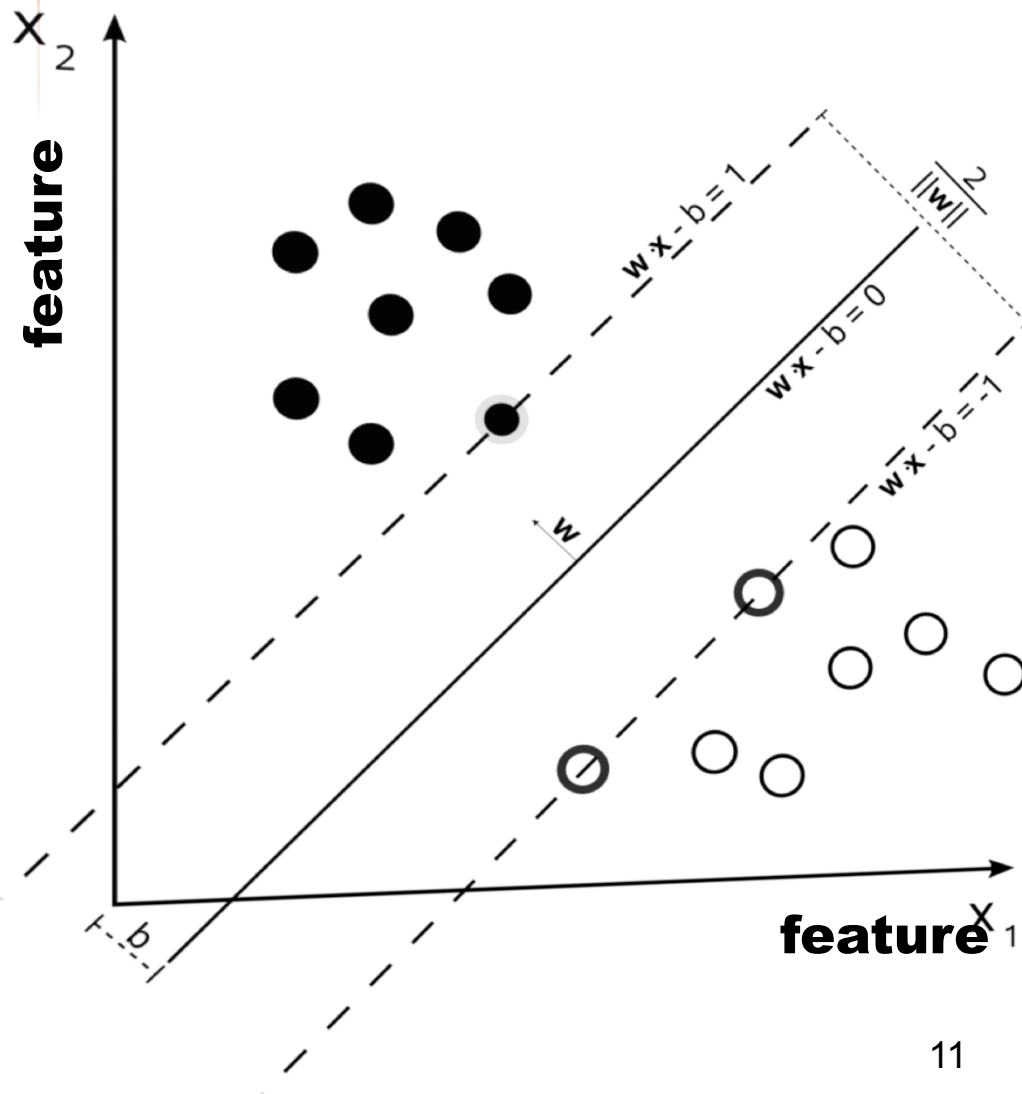
(c) Internal length

## ◆ Layout Fragmentation

- › With a pre-defined set of measurement operators
- › Accurate and very fast to apply (e.g., link to CALIBRE API)
- › Full detection to cover whole layout without samplings (cf. window-based approach)
- › Complexity and runtime scale  $O(n)$

# Machine Learning Kernel - SVM

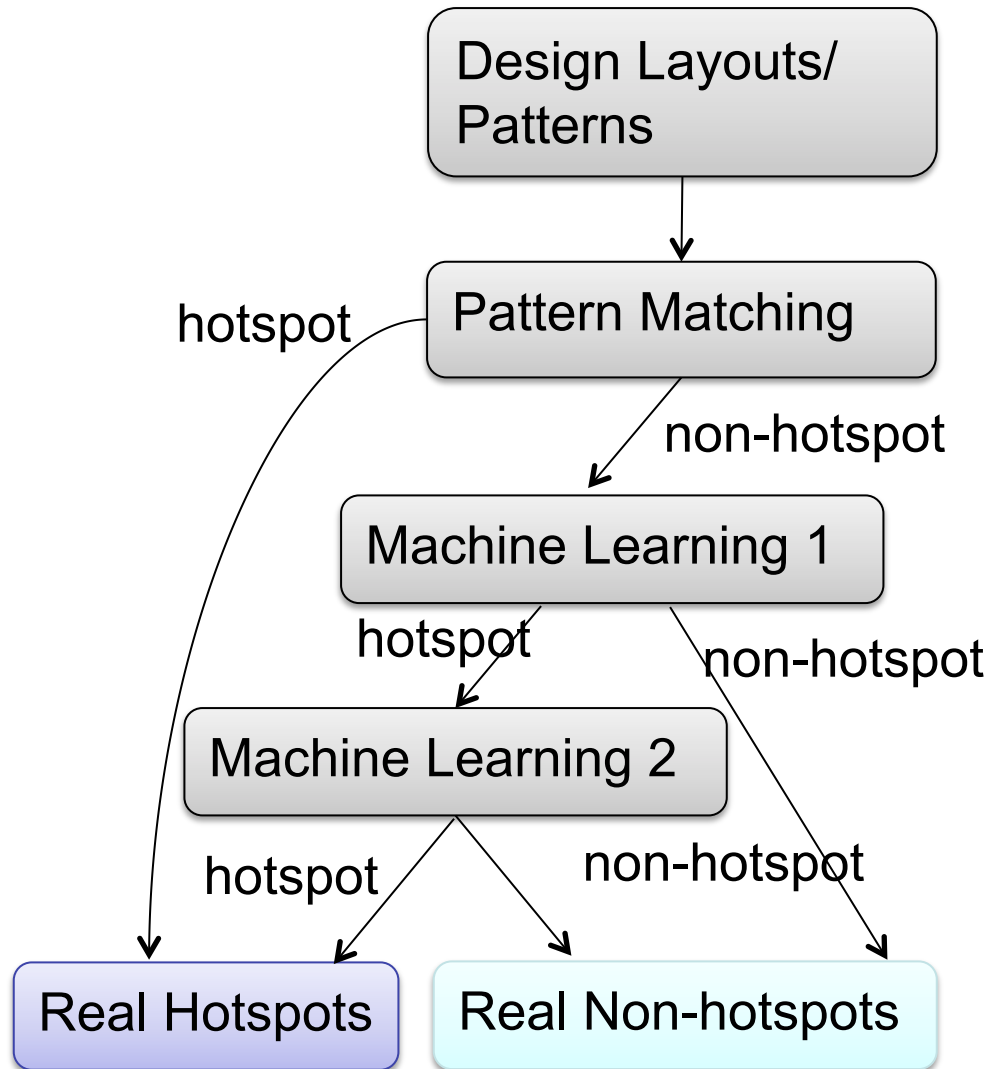
## ◆ Support Vector Machine – A linear separation demo



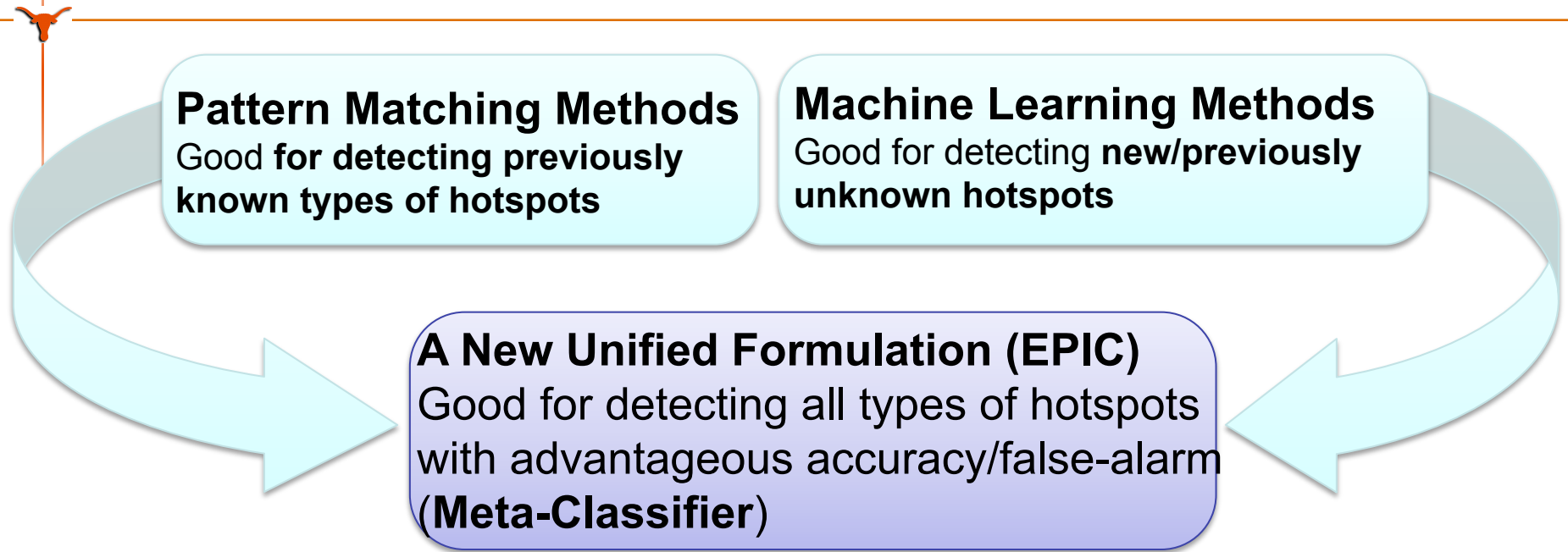
To maximize the separation margin

- ◆ Convert hotspot detection problem to a *binary classification problem* (hot or nonhot separation)
- ◆ Support Vector Machine can find a set of support vectors to construct a boundary plane that maximize the separation of 2 distinctive sets of data

# A Naïve Combination of ML and Pattern Matching



# Meta-Classification



- ◆ Meta-Classification combines the strength of different types of hotspot detection techniques

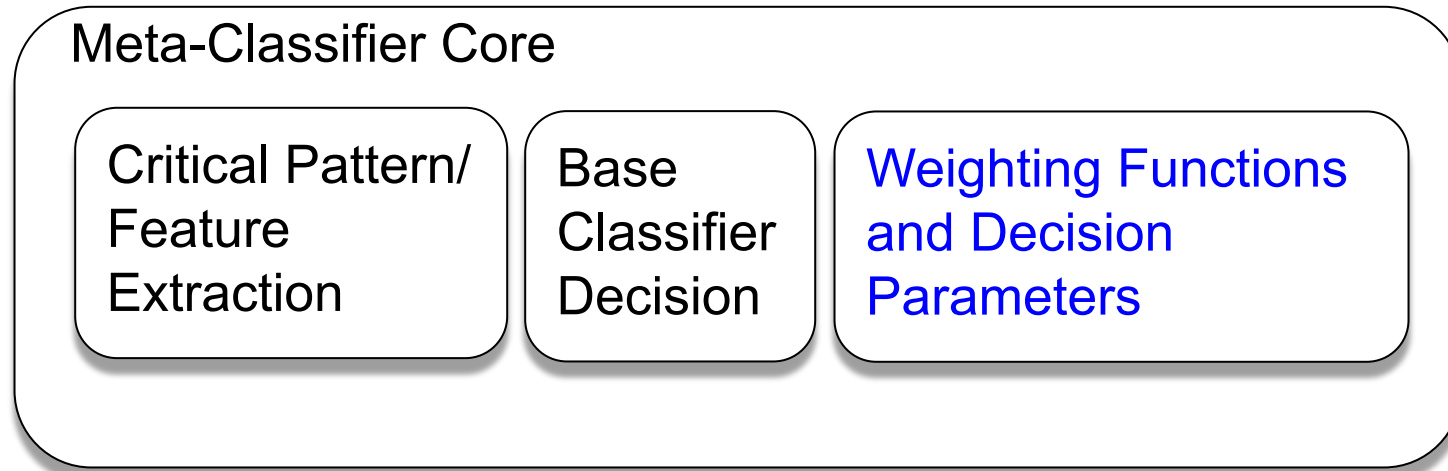
[Ding et al, ASPDAC 2012 BPA]

# An Illustrative Example



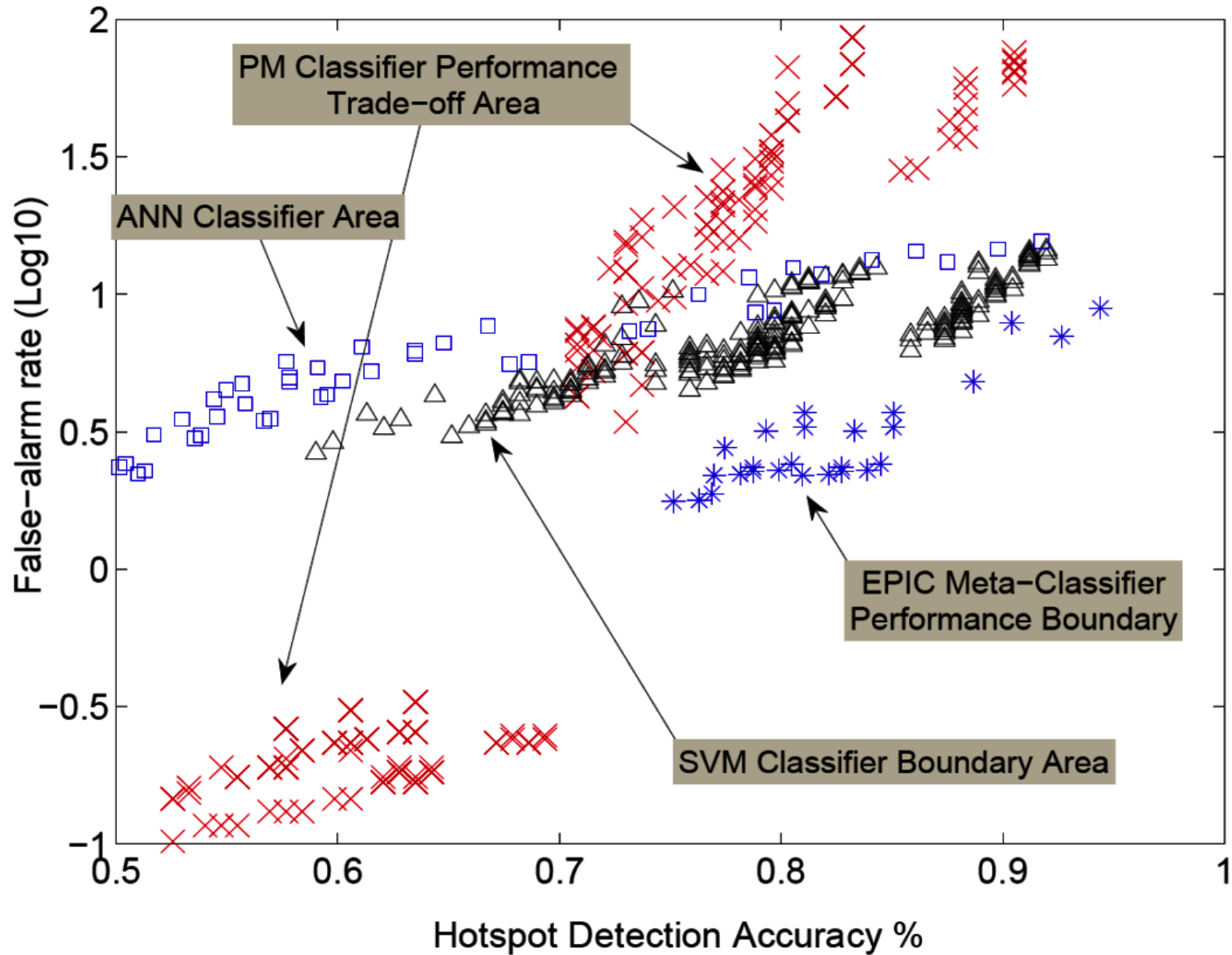
Detection Sub-block	Detection Results (H: hotspot, N: non-hotspot, X: Don't Care)				
Machine Learning 1	X	H	N	H	N
Machine Learning 2	X	H	H	N	N
Pattern Matching	H	N	N	N	N
<b>Final Decision</b>	H	H	N	<b>H</b>	N

# Components of Meta-Classifer Core



- ◆ Base classifier results are first collected
- ◆ Weighting functions to make the overall meta decision (e.g., Minimize Mean Square Error among all samples in data set)
  - › Quadratic Programming (QP) formulation
- ◆ Accuracy and false-alarm trade-off

# False-alarm Rate and Accuracy





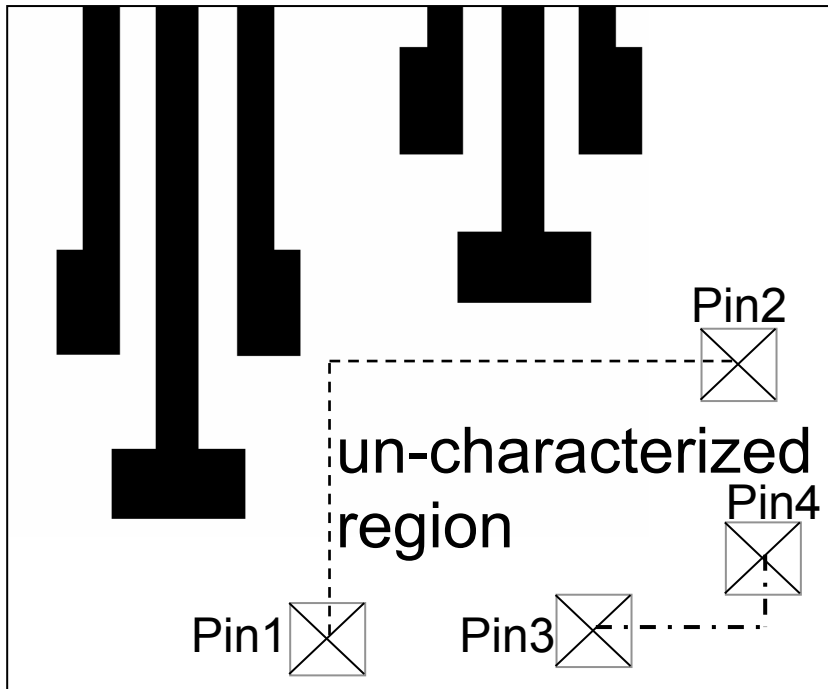
# ICCAD'12 Contest

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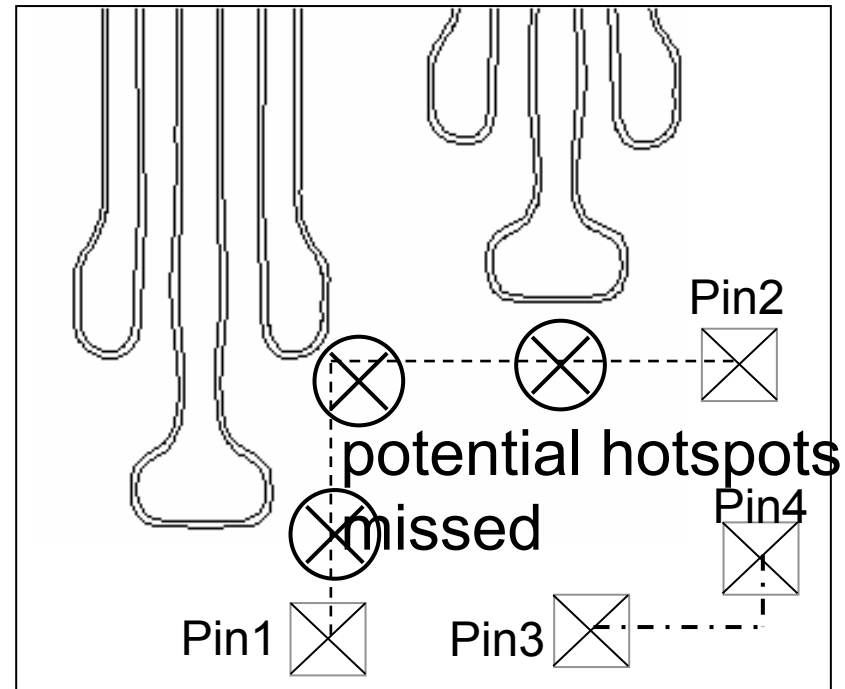
- ◆ Released benchmark by Mentor: 2D structures on metal layers with 32 to 28nm processes
- ◆ Desired target performance
  - › Low false alarm:  $< 100$  false hits/mm<sup>2</sup>
  - › Fast run time:  $< 1$  CPU-hr/mm<sup>2</sup>
  - › Detection accuracy:  $> 80\%$
  - › Portability: General calibration strategy
- ◆ Publications
  - › [Lin et al. DAC 2013]
  - › [Yu et al. DAC 2013]
  - › [Gao et al. SPIE 2014]
  - › .....

# Lithography-Friendly Detailed Routing

- ◆ [DAC'11] AENEID: Hotspot learning models in early design stage, used to guide routing

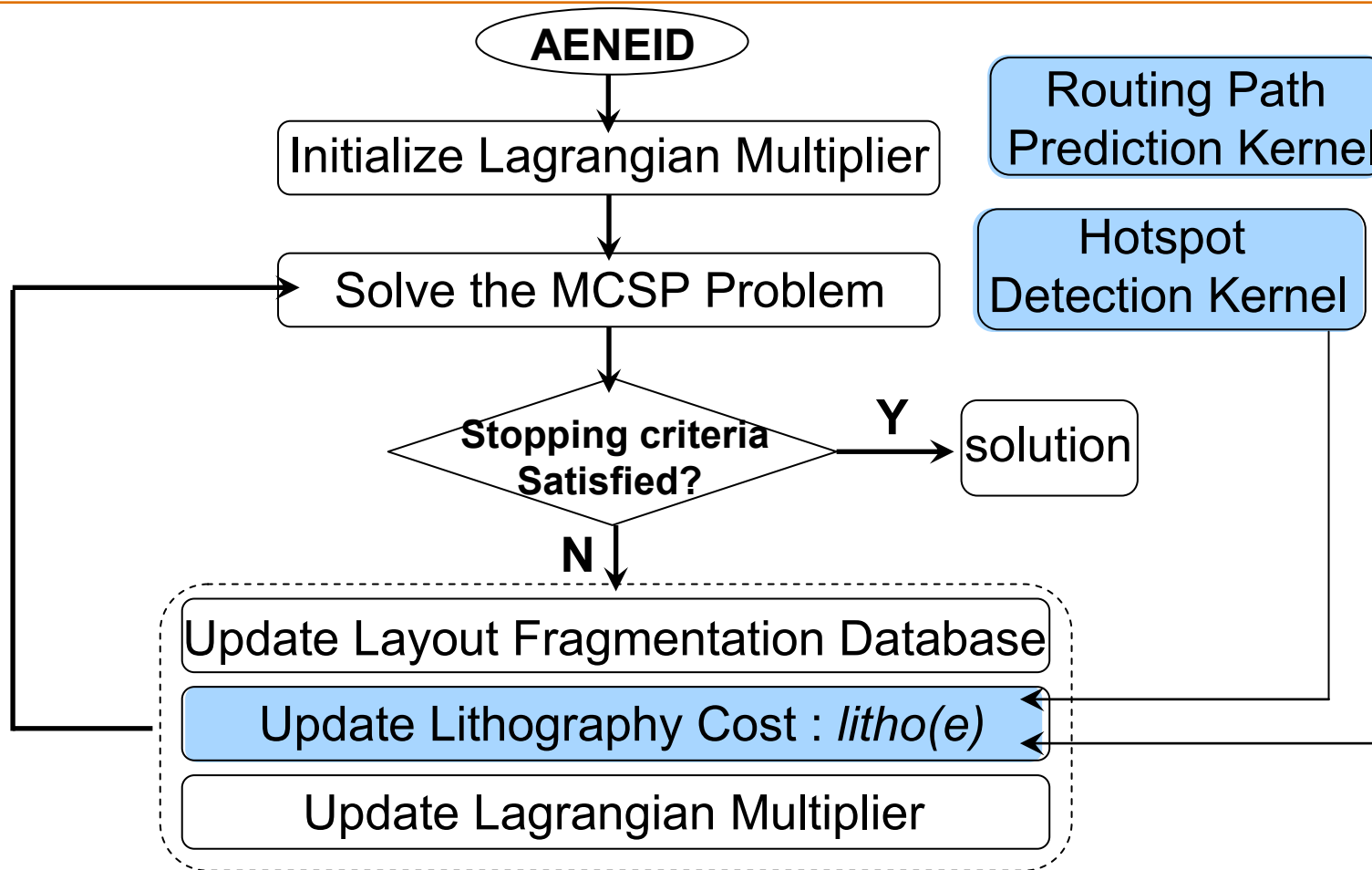


(a)



(b)

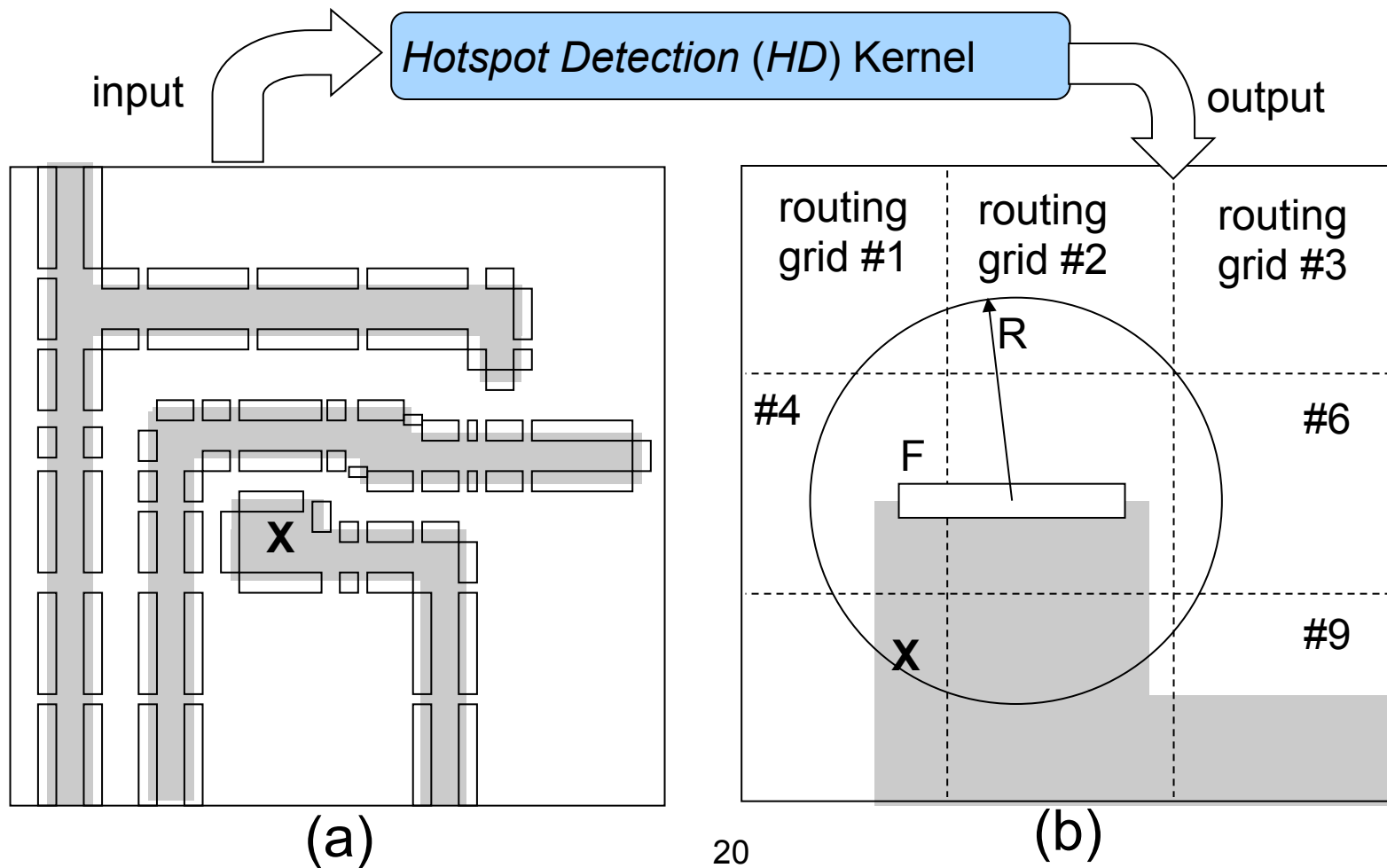
# AENEID Overall Flow



- ◆ Machine learning models to guide AENEID to avoid hotspot patterns in the early design stages

# Cost Function For Detailed Routing-I


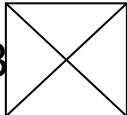
$$litho(e) = litho(e)^{HD} + litho(e)^{RPP}$$

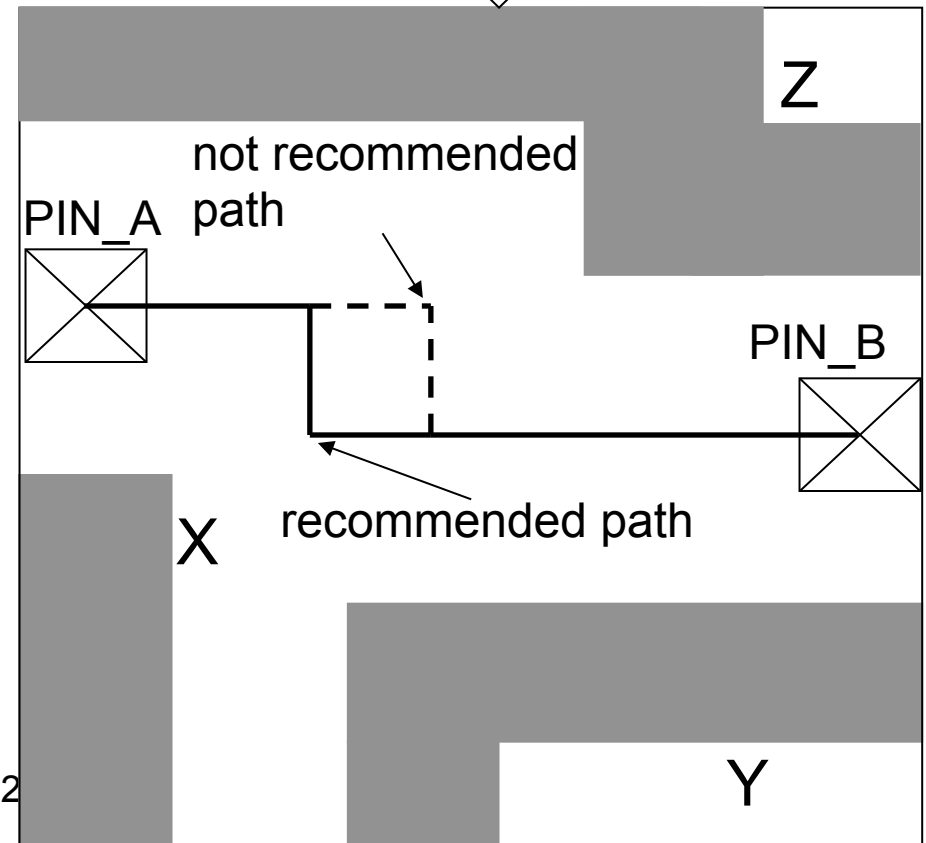


# Cost Function For Detailed Routing-II

$$litho(e) = litho(e)^{HD} + litho(e)^{RPP}$$

Routing Path Prediction  
(RPP) Kernel Processing

0.7	0.7	0.7	0.95	z0.3
0.55	0.00			
 PIN_A	0.00	0.00	0.45	0.5
0.2	0.00	0.00	PIN_B	
	X		0.00	
0.80	0.15	0.55	0.55	0.55
0.80	0.2	0.65	0.80	Y 0.80



# Testing Benchmarks and Simulation Results



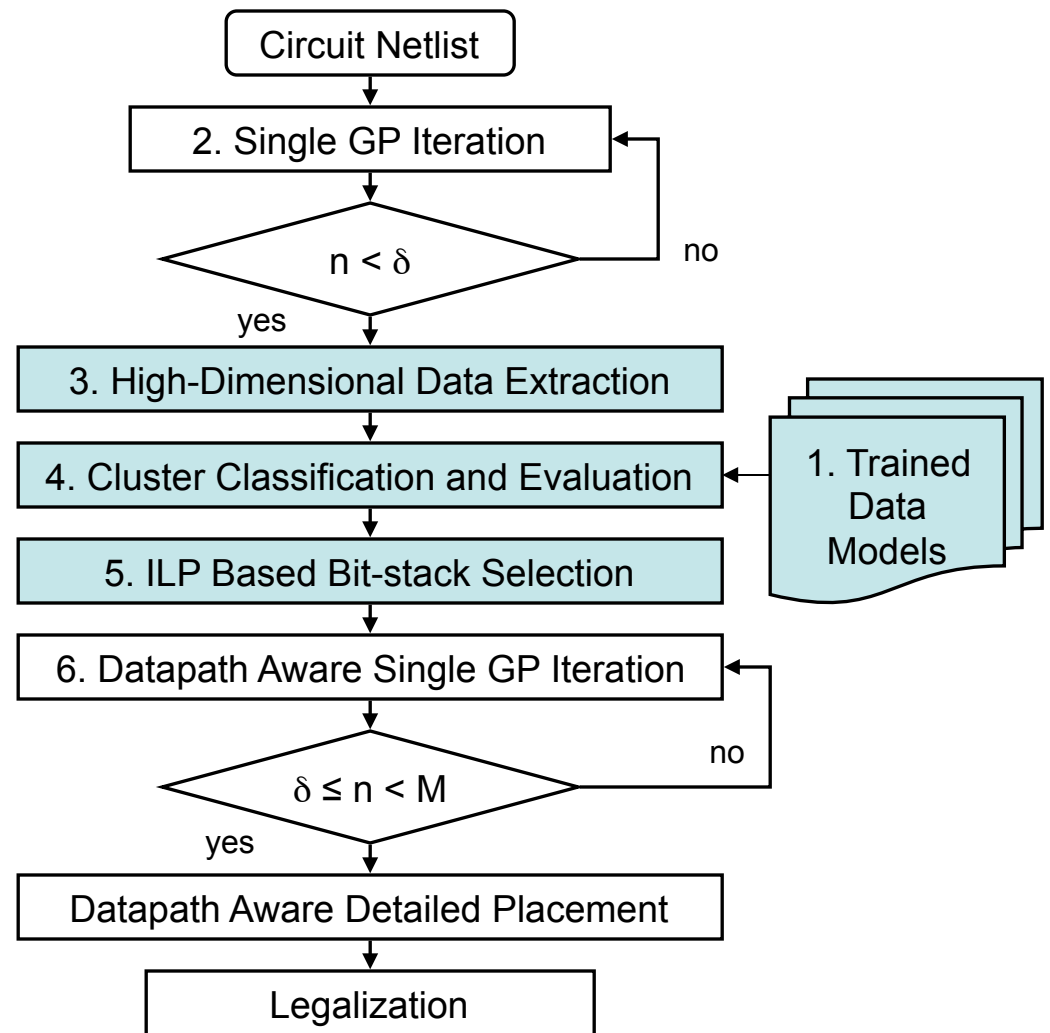
Benchmarks	CK1	CK2	CK3
Layout Size	50X50um <sup>2</sup>	100X100um <sup>2</sup>	160X160um <sup>2</sup>
Nets to Route	0.45K	1.48K	3.4K
M1 Blockage#	1K	8.8K	13.1K
M2 Fragment#	12.2K	41K	152.6K
M2 Blockage#	0.14K	0.47K	2K
M2 Fragment#	0.56K	1.9K	8.3K

Compared with ELIAD (Minsik Cho, et al. TCAD09), **AENEID** shows **23%-64%** hotspot reduction at the cost of **30%** extra run-time without penalty on total wire-length

	AENEID											
	HD						HD + RPP					
Circuit	CK1		CK2		CK3		CK1		CK2		CK3	
Circuit Size um <sup>2</sup>	50 <sup>2</sup>		100 <sup>2</sup>		160 <sup>2</sup>		50 <sup>2</sup>		100 <sup>2</sup>		160 <sup>2</sup>	
Wire-length um	859.3		5502.0		24797.0		859.1		5502.0		24797.5	
Run-time sec	8		409		3291		8		400		3279	
Run-time overhead %	33		38		19		33		35		18	
Metal layer	M1	M2	M1	M2	M1	M2	M1	M2	M1	M2	M1	M2
Hotspot#	11	2	34	7	90	17	8	2	22	5	58	15
Hotspot reduc %	35	33	48	30	44	26	53	33	66	50	64	35
Avg. hotspot reduc %	36						50					
Avg. extra run-time %	30						29					

# Machine Learning for Placement

- ◆ Data mining and extraction based on not just graph but also physical information
- ◆ We can extract datapath like structures even for “random” logics
- ◆ Use them to explicitly guide placement
- ◆ Very good results obtained cf. other leading placers like simPL, NTUPlace, mPL, CAPO



[Ward+, DAC' 12]

# Datapath Placement Techniques

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- ◆ Steiner wirelength (StWL) improvement through bit-stack alignment
  - › Significantly improves total StWL and routing congestion
- ◆ Datapath placement techniques
  - › Skewed Weighting with Step Size Scheduling
  - › Fixed-Point Alignment Constraint
  - › Bit-Stack Aligned Cell Swapping
  - › Datapath Group Repartitioning
- ◆ Integrate alignment constraints into force-directed placement
- ◆ Simultaneously place datapath & random logic

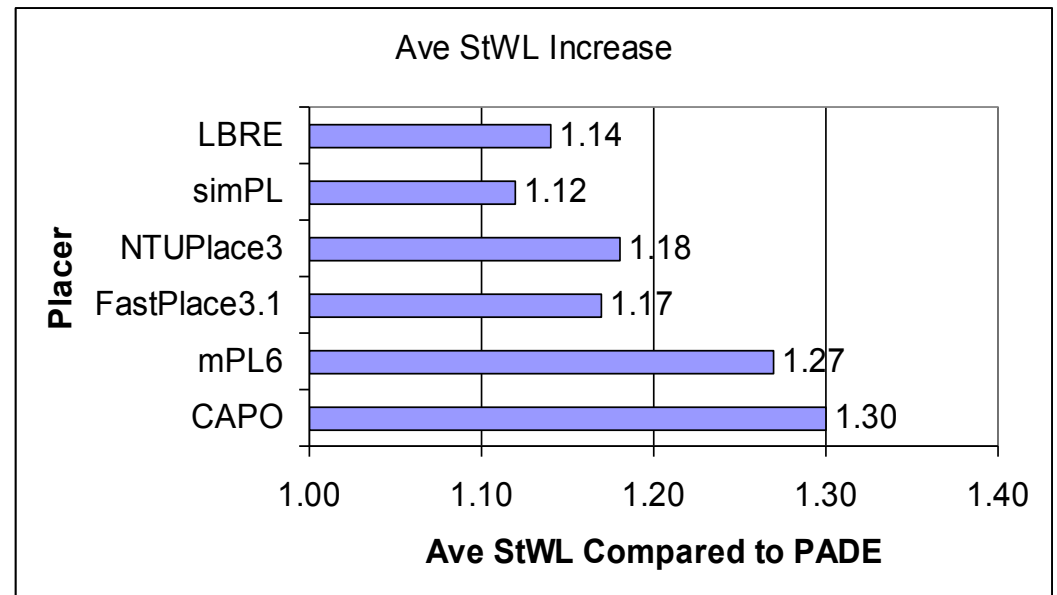
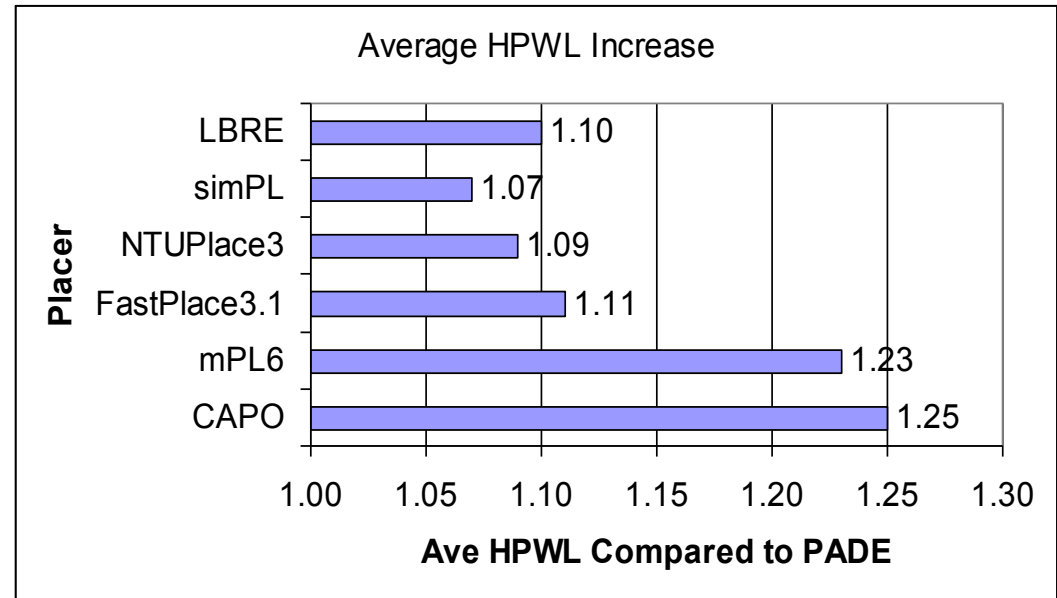
[Ward+, ISPD' 12]



# PADE: Hybrid Experimental Results



- ◆ All numbers are average wirelength ratio cf. PADE
- ◆ PADE without datapath extraction generates the simPL wirelength results
- ◆ HPWL: 7%+ better
- ◆ StWL: 12%+ better



# PADE: ISPD2005 Results

- ◆ PADE Wirelength results on the ISPD 2005 Placement Benchmarks
- ◆ At least 2% better in HPWL
- ◆ At least 3% better in StWL
- ◆ Highlights the effectiveness of structure aware extraction

	CAPO	mPL6	FastPlace3.1	NTUPlace3	simPL	PADE
Adaptec1	97.22	86.2	88.75	91.06	87.05	<b>85.12</b>
Adaptec2	114.54	100.64	104.03	99.06	102.13	<b>98.92</b>
Adaptec3	296.22	235.06	239.7	234.52	228.32	<b>222.08</b>
Adaptec4	257.47	208.85	215.02	211.86	201.82	<b>196.23</b>
Bigblue1	127.72	108.31	<b>105.24</b>	110.02	109.94	106.98
Bigblue2	189.6	174.69	178.44	175.27	168.65	<b>164.33</b>
Bigblue3	452.91	370.7	421.31	389.39	369.61	<b>361.96</b>
Bigblue4	1105.52	930.63	911.64	974.44	901.85	<b>883.82</b>
AVE	1.22	1.04	1.07	1.06	1.03	1.00

# Outline

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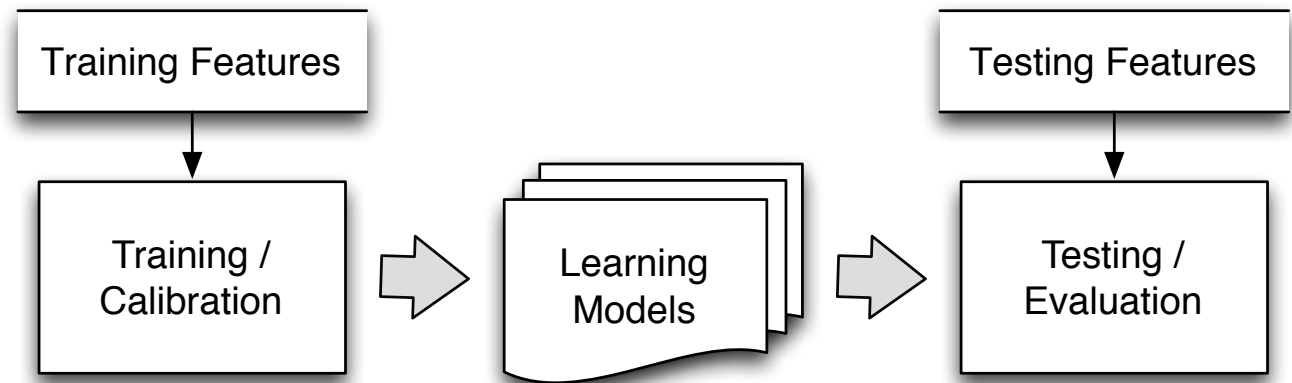


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- ◆ **Some Advanced Issues**
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# Issue 1: ML or PM?

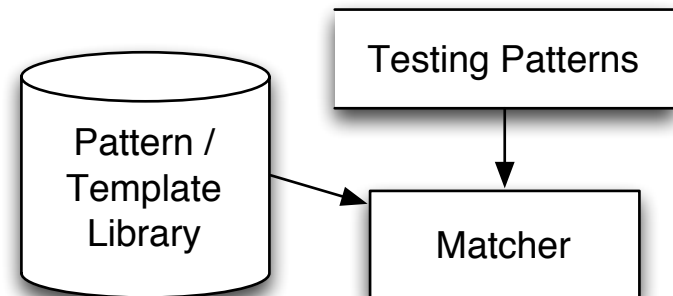
## Machine Learning:

- › (+) good to unseen data
- › (-) longer training time



## Pattern Matching:

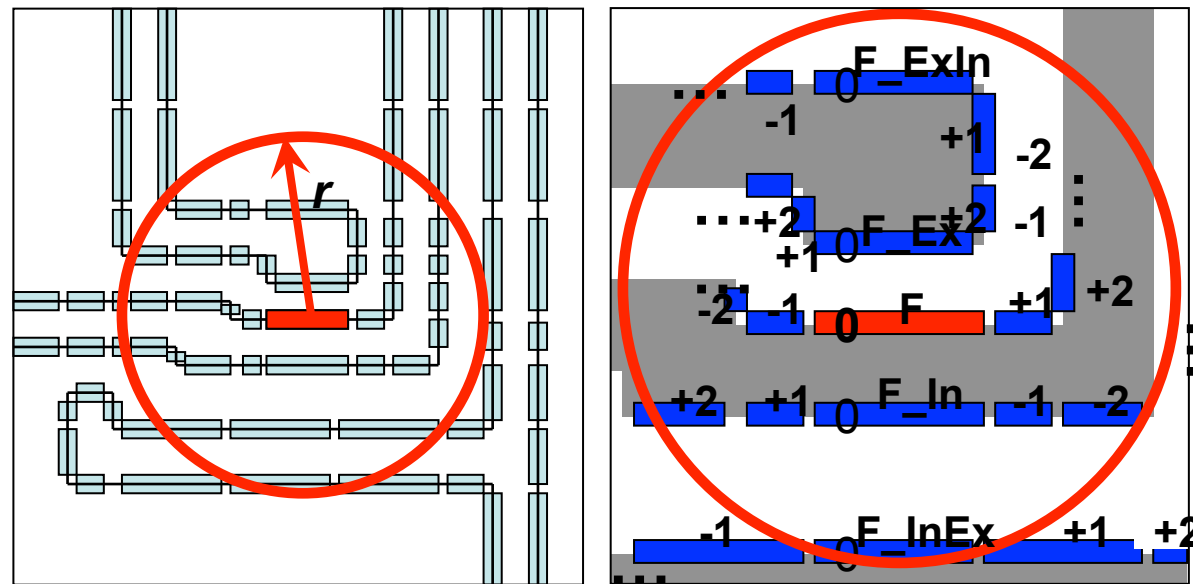
- › (+) Easy to implement, fast
- › (-) Sensitive to process change



Hybrid approaches are desirable!

# Issue 2: Feature Extraction

- ◆ Fragmentation based feature [ASPDAC'11, SPIE'14]



$$\tilde{F}_i \in \delta_r^F$$

$$V_F = \bigoplus_i \{f_{corn}(\tilde{F}_i) \oplus f_{ext}(\tilde{F}_i) \oplus f_{int}(\tilde{F}_i) \oplus f_{misc}(\tilde{F}_i)\}$$

$$\tilde{F} = [F, F\_Ex, F\_In, F\_InEx, F\_ExIn...]$$

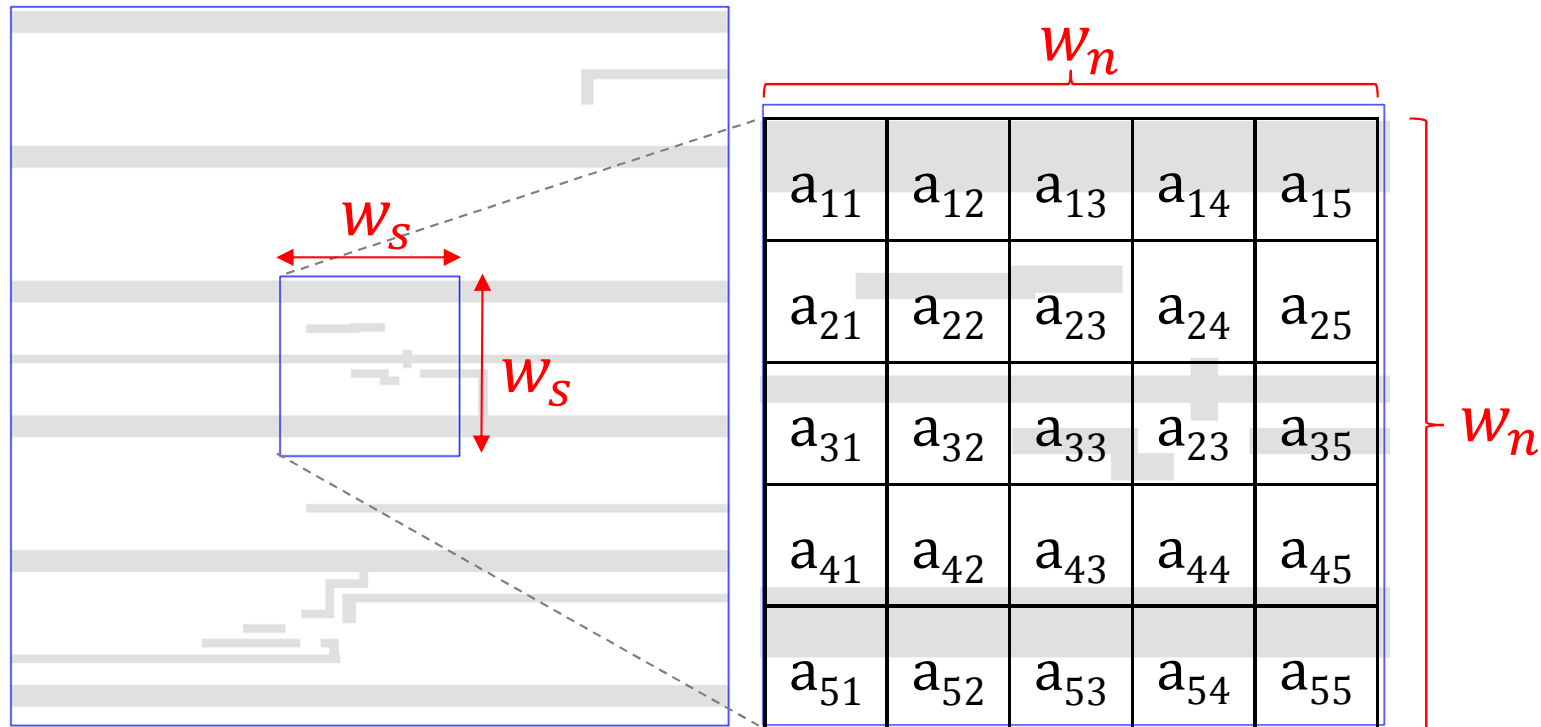
$V_F$  is the feature vector associated with *fragment*  $F$

$\bigoplus$  is a concatenate function;  $\oplus$  is a sort-n-combine function

$\delta_r^F$  includes both proximity and some peripheral information

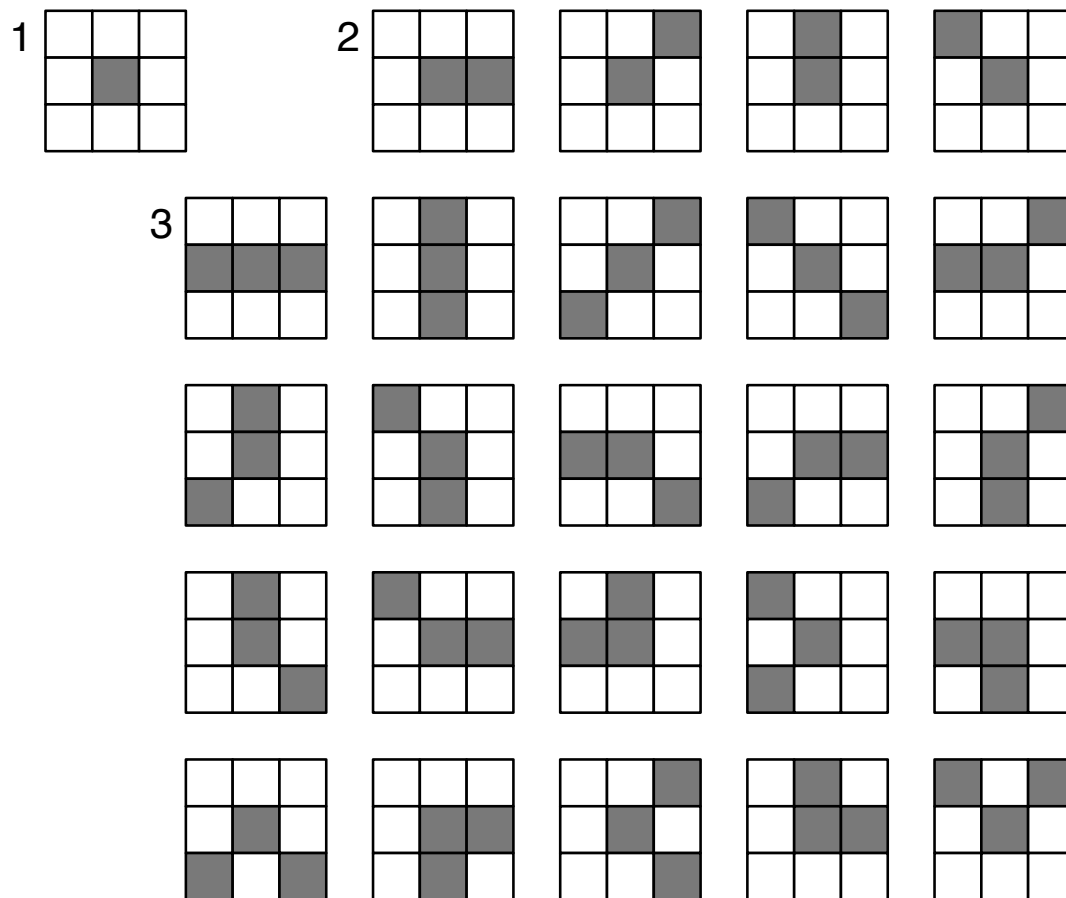
# Issue 2: Feature Extraction

- ◆ Density based feature [Wuu+, ASPDAC'11; Matsunawa +, SPIE'15]



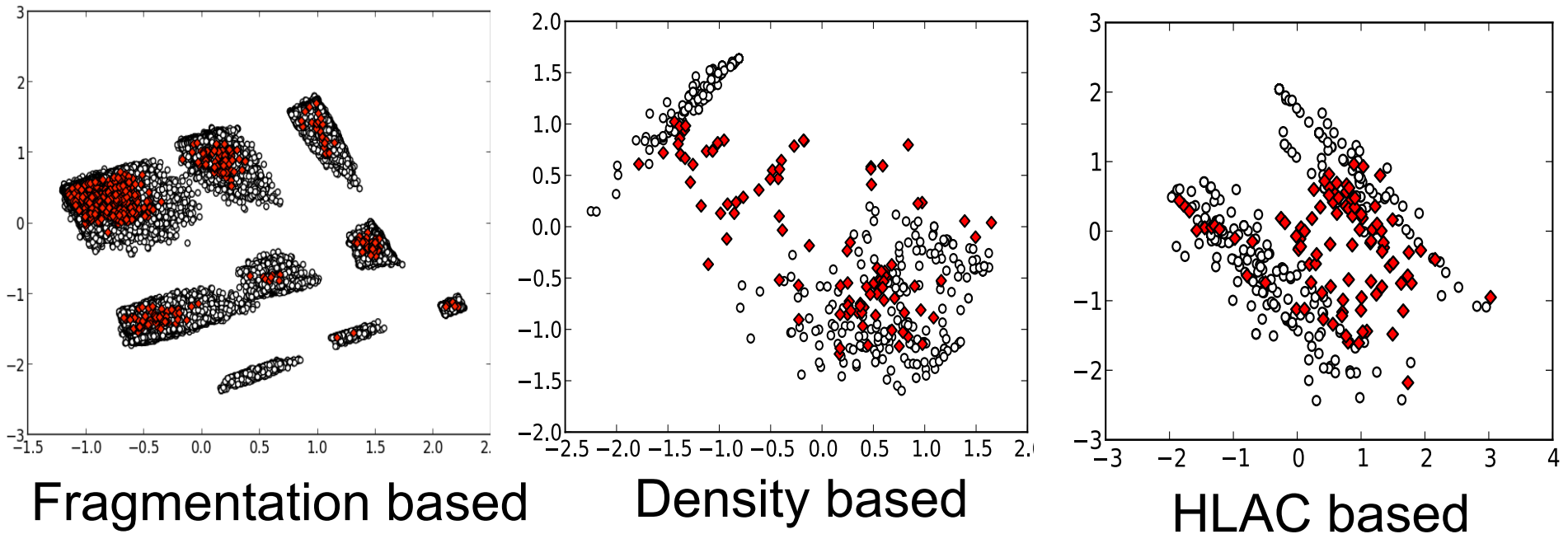
# Issue 2: Feature Extraction (cont.)

- ◆ HLAC based feature [Nosato+, JM3'14]
  - › higher-order local autocorrelation (HLAC)
  - › 25 local masks => 25 dimensional vector feature



# Issue 2: Feature Evaluation

## ◆ Analyze Feature Space



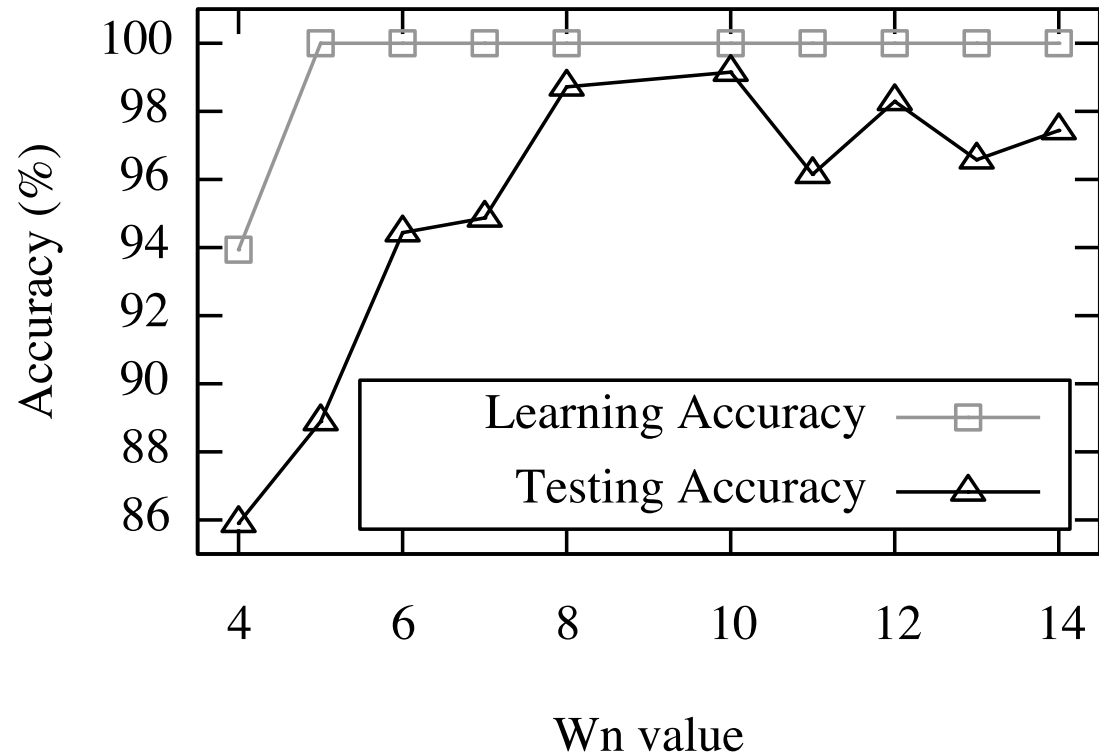
## ◆ Measure feature distances [Matsunawa+, SPIE'15]

$$d_i = \frac{\sqrt{(x_i - \mu)^T V^{-1} (x_i - \mu)} - d_{NHS_{min}}}{d_{NHS_{max}} - d_{NHS_{min}}}$$



# Issue 3: Overcome Overfitting

- ◆ Overfitting: good training, but bad testing



- ◆ Possible Solutions:

- › Regularization (additional constraints or objective terms)
- › Cross validation

# Conclusion

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- ◆ Machine learning and pattern matching 101
- ◆ Applications in VLSI design and verification
  - › Lithography hotspot detection
  - › Lithography friendly routing
  - › Datapath-like circuit extraction and placement
- ◆ Still many open problems and opportunities
  - › Hybrid machine learning and pattern matching
  - › Feature extraction and classification
  - › Overfitting in machine learning
  - › Cross-layer applications